

L Number	Hits	Search Text	DB	Time stamp
1	0	((((ammonia NH3) with ("hydrogen peroxide" H2O2) ) and ((ammonia NH3) same ("hydrogen peroxide" H2O2) ) and ("silicon oxide" "silicon nitride")) and @py<2000) and heat\$3 and (HNO3 Nitric Acid)	USPAT	2002/12/04 09:54
2	0	((((ammonia NH3) with ("hydrogen peroxide" H2O2) ) and ((ammonia NH3) same ("hydrogen peroxide" H2O2) ) and ("silicon oxide" "silicon nitride")) and @py<2000) and heat\$3 and (HNO3 Nitric Acid)	US-PGPUB; EPO; JPO	2002/12/04 09:54
-	7604	PVD or ("physical vapor deposition")	USPAT	2002/04/15 14:41
-	1	(PVD or ("physical vapor deposition")) and "shutter disk"	USPAT	2002/04/14 15:20
-	199	(PVD or ("physical vapor deposition")) and shutter	USPAT	2002/04/14 15:21
-	1	((PVD or ("physical vapor deposition")) and shutter) and pasting	USPAT	2002/04/14 15:21
-	66	((PVD or ("physical vapor deposition")) and shutter) and cover	USPAT	2002/04/14 15:23
-	0	((PVD or ("physical vapor deposition")) and shutter) and cover) and "cover ring"	USPAT	2002/04/14 15:22
-	13	((PVD or ("physical vapor deposition")) and shutter) and cover) and wafer	USPAT	2002/04/14 15:23
-	245960	ammonia hydrazine amine NH3	USPAT	2002/04/15 14:58
-	1751	(ammonia hydrazine amine NH3) and (tetraethylorthosilicate TEOS)	USPAT	2002/04/15 14:59
-	1369	((ammonia hydrazine amine NH3) and (tetraethylorthosilicate TEOS)) and ("hydrogen peroxide" ozone oxygen "nitric acid" "sulfuric acid" H2O2 O3 H2SO4)	USPAT	2002/04/15 15:00
-	796	((ammonia hydrazine amine NH3) and (tetraethylorthosilicate TEOS)) and ("hydrogen peroxide" ozone oxygen "nitric acid" "sulfuric acid" H2O2 O3 H2SO4)) and ("silicon oxide" "silicon nitride")	USPAT	2002/04/15 15:01
-	593	((ammonia hydrazine amine NH3) and (tetraethylorthosilicate TEOS)) and ("hydrogen peroxide" ozone oxygen "nitric acid" "sulfuric acid" H2O2 O3 H2SO4)) and ("silicon oxide" "silicon nitride")) and (insulator insulating)	USPAT	2002/04/15 15:39

-	170	(((((ammonia hydrazine amine NH3) and (tetraethylorthosilicate TEOS)) and ("hydrogen peroxide" ozone oxygen "nitric acid" "sulfuric acid" H2O2 O3 H2SO4)) and ("silicon oxide" "silicon nitride"))) and (insulator insulating)) and (film near forming)	USPAT	2002/04/16 12:50
-	170	(((((ammonia hydrazine amine NH3) and (tetraethylorthosilicate TEOS)) and ("hydrogen peroxide" ozone oxygen "nitric acid" "sulfuric acid" H2O2 O3 H2SO4)) and ("silicon oxide" "silicon nitride"))) and (insulator insulating)) and (film near forming)) and silicon	USPAT	2002/04/15 15:42
-	91	(((((ammonia hydrazine amine NH3) and (tetraethylorthosilicate TEOS)) and ("hydrogen peroxide" ozone oxygen "nitric acid" "sulfuric acid" H2O2 O3 H2SO4)) and ("silicon oxide" "silicon nitride"))) and (insulator insulating)) and (film near forming)) and silicon and (water H2O)	USPAT	2002/04/15 15:47
-	60	((((((ammonia hydrazine amine NH3) and (tetraethylorthosilicate TEOS)) and ("hydrogen peroxide" ozone oxygen "nitric acid" "sulfuric acid" H2O2 O3 H2SO4)) and ("silicon oxide" "silicon nitride"))) and (insulator insulating)) and (film near forming)) and silicon and (water H2O)) and "silicon nitride" and "silicon oxide"	USPAT	2002/04/16 11:44
-	23	((((((ammonia hydrazine amine NH3) and (tetraethylorthosilicate TEOS)) and ("hydrogen peroxide" ozone oxygen "nitric acid" "sulfuric acid" H2O2 O3 H2SO4)) and ("silicon oxide" "silicon nitride"))) and (insulator insulating)) and (film near forming)) and silicon and (water H2O)) and "silicon nitride" and "silicon oxide" and "hydrogen peroxide"	USPAT	2002/04/16 12:49
-	3780	((ammonia hydrazine amine NH3) and ("hydrogen peroxide" H2O2)) and ("dangling bonds" "hydroxyl groups" "interface bonds")	USPAT	2002/04/16 12:52
-	100	((ammonia hydrazine amine NH3) and ("hydrogen peroxide" H2O2)) and ("dangling bonds" "hydroxyl groups" "interface bonds")) and "silicon nitride"	USPAT	2002/04/16 12:53
-	47	((ammonia hydrazine amine NH3) and ("hydrogen peroxide" H2O2)) and ("dangling bonds" "hydroxyl groups" "interface bonds")) and "silicon nitride" and "silicon oxide"	USPAT	2002/12/03 16:33
-	2565	(ammonia NH3) same ("hydrogen peroxide" H2O2)	USPAT	2002/12/03 16:35
-	467	((ammonia NH3) same ("hydrogen peroxide" H2O2) ) and ("silicon oxide" "silicon nitride")	USPAT	2002/12/03 16:35
-	1541	(ammonia NH3) with ("hydrogen peroxide" H2O2)	USPAT	2002/12/03 16:35

-	407	((ammonia NH3) with ("hydrogen peroxide" H2O2) ) and (((ammonia NH3) same ("hydrogen peroxide" H2O2) ) and ("silicon oxide" "silicon nitride"))	USPAT	2002/12/03 16:36
-	239	((ammonia NH3) with ("hydrogen peroxide" H2O2) ) and (((ammonia NH3) same ("hydrogen peroxide" H2O2) ) and ("silicon oxide" "silicon nitride"))) and @py<2000	USPAT	2002/12/03 16:41
-	201	((ammonia NH3) with ("hydrogen peroxide" H2O2) ) and (((ammonia NH3) same ("hydrogen peroxide" H2O2) ) and ("silicon oxide" "silicon nitride"))) and @py<2000) and heat\$3	USPAT	2002/12/04 09:53